



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Pan et al.

Serial No.: 09/614,113

Filed: July 12, 2000

For: TECHNIQUE FOR ELIMINATION OF PITTING ON SILICON SUBSTRATE

DURING GATE STACK ETCH

Confirmation No.: 1710

Examiner: C. Brown

Group Art Unit: 1765

Attorney Docket No.: 2915.3US

(96-0149.2)

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CERTIFICATE OF MAILING

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Amanda Holland

Typed/printed name of person whose signature is contained above

RESPONSE TO OFFICE ACTION

Commissioner for Patents Washington, D.C. 20231

Sir:

The following remarks are filed in response to the Examiner's remarks in the Office Action mailed October 23, 2002, the three-month shortened statutory period for response to which expired on January 23, 2003. Enclosed herewith is a Petition for One-Month Extension of Time and accompanying fee under 37 C.F.R. § 1.17(a)(1).